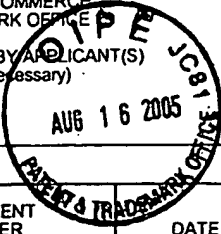
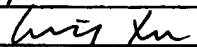


FORM PTO 1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)				ATTY DOCKET NO. <b>03500.017112</b>		APPLICATION NO. <b>10/653,978</b>	
				APPLICANT <b>Kazuhiko Fukutani et al.</b>			
				FILING DATE <b>September 4, 2003</b>		GROUP <b>1775</b>	
U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
LX		6,610,463 B1	08/26/03	Ohkura et al.	430	322	08/29/00
		2004/0001964 A1	01/01/04	Ohkura et al.	428	596	08/29/00
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		2005/0053773 A1	03/10/05	Fukutani et al.	428	209	08/06/04
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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
LX	JP	2001-273622	10/05/01	Japan			Abstract
	JP	52-78403	07/01/77	Japan			No
	JP	62-270473	11/24/87	Japan			Translation No
	JP	63-220411	09/13/88	Japan			Translation No
	JP	7-73429	03/17/95	Japan			Abstract
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)							
LX		M. Jacobs et al., "Unbalanced Magnetron Sputtered Si-Al Coatings: Plasma Conditions and Film Properties Versus Sample Bias Voltage," 116-119 <u>Surface and Coatings Technology</u> 735-41 (1999).					
		C.D. Adams et al., "Phase Separation During Co-Deposition of Al-Ge Thin Films," 7(3) <u>J. Mater. Res.</u> 653-67 (March 1992).					
		C.D. Adams et al., "Transition from Lateral to Transverse Phase Separation During Film Co-deposition," 59(20) <u>Appl. Phys. Lett.</u> 2535-37 (November 1991).					
		M. Atzmon et al., "Phase Separation During Film Growth," 42(2) <u>J. Appl. Phys.</u> 442-46 (July 1992).					
EXAMINER				DATE CONSIDERED			
				<b>9/14/05</b>			

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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				APPLICANT <b>Kazuhiko Fukutani et al.</b>			
				FILING DATE <b>September 4, 2003</b>		GROUP <b>1775</b>	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
LX		6,027,796	02/22/00	Kondoh et al.	428	312.8	

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		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
LX	JP	9-157062	06/17/97	Japan			Translation
↓	JP	2001-261376	09/26/01	Japan			Translation
	WO	03/069677 A1	08/21/03	International			
	WO	03/078685 A1	09/25/03	International			Abstract
↓	JP	2001-101644	04/13/01	Japan			Abstract

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)		
LX		C.D. Adams, et al. "Monte Carlo Simulation of Phase Separation During Thin-Film Codeposition," 74(3) J. Appl. Phys. 1707-15 (August 1993).

EXAMINER <i>Wing Xu</i>	DATE CONSIDERED <i>9/14/05</i>
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